FORM PTO 1449 (modified)  U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE  OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary)  Submitted: November 25, 2003			ATTY DOCKET NO. 03500.010530.4	APPLICATION NO.	APPLICATION NO. 09/161,774		
			APPLICANT  KIYOFUMI SAKAGUCHI, ET AL.				
			FILING DATE September 29, 1998		GROUP 2823		
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(É	4,116,751	09/26/78	Zaromb	156	600		
	4,727,047	02/23/88	Bozler, et al.	437	89		
	5,248,621	09/28/93	Sano	437	3		
	5,250,460	10/05/93	Yamagata, et al.	437	62		
	5,277,748	01/11/94	Sakaguchi, et al.	156	630		
	5,278,092	01/11/94	Sato	437	90		
	5,278,093	01/11/94	Yonehara	437	109		
	5,285,078	02/08/94	Mimura, et al.	257	3		
	5,290,712	03/01/94	Sato, et al.	437	24		
	5,320,907	06/14/94	Sato	428	446		
	5,331,180	07/19/94	Yamada, et al.	257	3		
	5,362,683	11/08/94	Takenaka, et al.	437	226		
	5,363,793	11/15/94	Sato	117	2	<u> </u>	
	5,371,037	12/06/94	Yonehara	437	86	····	
	5,374,564	12/20/94	Bruel	437	24		
	5,403,771	04/04/95	Nishida, et al.	437	89		
	5,433,168	07/18/95	Yonehara	117	90		
	5,453,394	09/26/95	Yonehara, et al.	437	62		
	5,457,058	10/10/95	Yonehara	437	24		
	5,459,081	10/17/95	Kajita	437	3		
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	5,536,361	07/16/96	Kondo, et al.	156	630.1		
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<sup>\*</sup>EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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10 2 5 2000 E	5,670,411	09/23/97	Yonehara, et al.	437	62		
CATE TRADE	5,811,348	09/22/98	Matsushita, et al.	438	455		
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## FORM PTO 1449 (modified) ATTY DOCKET NO. APPLICATION NO. 03500.010530.4 09/161,774 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE APPLICANT KIYOFUMI SAKAGUCHI, ET AL. LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary) FILING DATE GROUP Submitted: November 25, 2003 2823 **September 29, 1998** FOREIGN PATENT DOCUMENTS \*EXAMINER TRANSLATION DOCUMENT DATE COUNTRY CLASS SUBCLASS YES/NO/ NUMBER OR ABSTRACT 0553860 A2 08/04/93 **EPO** 0554795 A1 08/11/93 **EPO** EP 0584777 A1 03/02/94 **EPO** EP 0618624 A2 10/05/94 **EPO** EP 0757377 A2 02/05/97 **EPO** EP 0793263 A2 09/03/97 **EPO** EP 0797258 A2 09/24/97 **EPO** GB 2211991 A 07/12/89 United Kingdom JP 60-196955 V 10/05/85 Abstract Japan ĴΡ Abstract 05/19/87 62-108539 \/ Japan Part Tran. JP 62-279625 12/04/87 Japan JP 03-70156 03/26/91 **Abstract** Japan Abstract JP. 05-211128 08/20/93 Japan Translation JP 05-283722 10/29/93 Japan

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**Translation** 

**Abstract** 

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			APPLICANT  KIYOFUMI SAKAGUCHI, ET AL.					
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LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary)		APPLICANT  KIYOFUMI SAKAGUCHI, ET AL.					
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